

Docket Number: 081468-0305376

Client Reference: P-0362.010-US



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of FRANCISCUS

BERNARDUS MARIA VAN BILSEN, et al. Group Art Unit: 2878

Application No.: 10/665,404

Examiner: Stephone B. Allen

Filed: September 22, 2003

Confirmation No.: 4408

For: ALIGNMENT SYSTEMS AND METHODS FOR LITHOGRAPHIC SYSTEMS

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR 1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. Copies of cited U.S. patents and patent application publications are not included. Copies of foreign patent documents and non-patent literature are included. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom. Applicants respectfully request the Examiner return an initialed copy of the enclosed Form PTO-1449 to Applicants with the next Office communication to indicate that the references have been considered, per MPEP § 609.

This Information Disclosure Statement is being filed more than three months after the U.S. filing date AND after the mailing date of the first Office Action on the merits, but before the mailing date of a Final Rejection or Notice of Allowance.

Please charge Deposit Account 033975 in the amount of \$180.00 in payment of the fee under 37 CFR 1.17(p). Please credit or debit Deposit Account 033975 as needed to ensure consideration of the disclosed information.



Application No. 10/665,404
Atty. Docket No. 081468-0305376

The patents, publications, or other information listed on the attached PTO-1449 are in the English language and therefore, do not require a statement of relevancy.

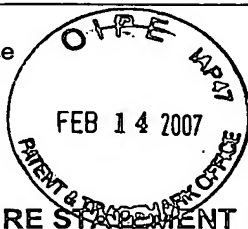
JP 3-257303 and DD 262 510 cited on the PTO-1449 are attached with English language Abstracts.

Respectfully Submitted,

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**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Atty. Dkt. No.	M#	Client Ref.
081468	0305376	P-0362.010-US
Applicant: VAN BILSEN et al.		
Appln. No.: 10/665,404		
Filing Date: September 22, 2003		
Examiner: Stephone B. Allen		Group Art Unit: 2878

Date: February 14, 2007 Page 1 of 1

U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	AR	4,356,392	10/1982	Wittekoek et al.			
	BR	4,596,467	06/1986	Bartelt			
	CR	4,737,283	04/1988	Gresch			
	DR	5,047,651	09/1991	Wessner et al.			
	ER	5,381,210	01/1995	Hagiwara et al.			
	FR	5,424,548	06/1995	Puisto			
	GR	5,995,198	11/1999	Mizutani			
	HR	6,384,899 B1	05/2002	Den Boef			
	IR	6,762,111 B2	07/2004	Fukoda			
	JR	6,864,956 B1	03/2005	Teong et al.			
	KR	6,937,344	08/2005	Monshouwer et al.			
	LR	7,109,508 B2	09/2006	Shiraishi			
	MR	2001/0026368	10/2001	Mikami			
	NR	2002/0041373	04/2002	Littau et al.			
	OR	2002/0072003	06/2002	Brill et al.			

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor or Assignee Name	English Abstract		Translation Readily Available	
						Enclosed	No	Enclose	No
	PR	02/052350 A1	07/04/2002	PCT	Monshouwer et al.			X	
	QR	02/065545 A2	08/22/2002	PCT	Sezginer et al.			X	
	RR	0 164 165 B1	02/24/1988	European Patent Office	Van Der Werf			X	
	SR	0 467 445 B1	01/20/1999	European Patent Office	Van Den Brink et al.			X	
	TR	1 256 849 A1	11/13/2002	European Patent Office	Baselmans			X	
	UR	3-257303	11/15/1991	Japan	Keiichiro TONAI	X			
	VR	DD 262 510	11/30/1988	Germany	VEB Carl Zeiss Jena	X			
	WR								

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

XR	Ramon Navarro, et al., "Extended ATHENA™ alignment performance and application for the 100 nm technology node", Metrology, Inspection, and Process for Microlithography XV, Proceedings of SPIE, Vol. 4344 (2001)			X	
YR					

Examiner Date Considered:

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.